

Docket Number: 081468-0306524
Client Reference: P-0381.020-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Group Art Unit:

Application No.: TO BE ASSIGNED

Examiner:

Filed: November 12, 2003

Confirmation No.:

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

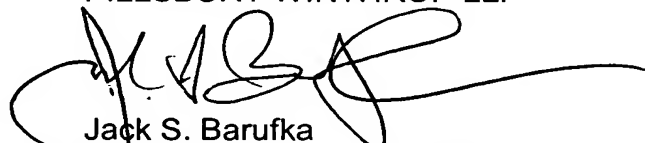
Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

PILLSBURY WINTHROP LLP



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Date: November 12, 2003

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Atty. Dkt. No.	M#	Client Ref.
	306524	P-0381.020-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF *et al.*

Appln. No.: TO BE ASSIGNED

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Examiner: Unknown Group Art Unit: Unknown

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	AR 3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
	BR 3,648,587	03/1972	Stevens	95	44	
	CR 4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
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						Enclosed	No	Enclose	No
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	PR EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>		X			
	QR EP 0418427	03/1991	Europe	Miyake		X		X	
	RR EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>		X		X	
	SR DD 224448	07/1985	German	Hesse <i>et al.</i>			X		
	TR DD 242880	02/1987	German	Kuch			X		
	UR FR 2474708	07/1981	France	Letellier			X		
	VR JP 62-065326	03/1987	Japan	Moriuchi		X			
	WR JP 62-121417	06/1987	Japan	Nakazawa		X			
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YR	EP Search Report for EP 02257938 dated September 25, 2003				
ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001				
AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356				
BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002				

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty. •
Dkt. No.

M#

Client Ref.

306781

P-0381.010-US

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of

3

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Group Art Unit: Unknown

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	CCR	6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
	DDR	6,633,365	10/2003	Suenaga	355	53	
	EER	2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
	FFR	2003/0123040	07/2003	Almog	355	69	
	GGR	2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	HHR						
	IIR						
	JJR						
	KKR						
	LLR						
	MMR						
	NNR						
	OOR						
	PPR						

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	QQR	JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>		X			
	RRR	JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>		X			
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	XXR	JP 10-340846	12/1998	Japan	Kudo		X		X	
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	DDD					
	EEE					

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